



# UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE  
United States Patent and Trademark Office  
Address: COMMISSIONER FOR PATENTS  
P.O. Box 1450  
Alexandria, Virginia 22313-1450  
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
-----------------	-------------	----------------------	---------------------	------------------

10/618,113

07/11/2003

Rajeev Joshi

11948.21

8697

27966

7590

02/01/2005

KENNETH E. HORTON

KIRTON & MCCONKLE

60 EAST SOUTH TEMPLE

SUITE 1800

SALT LAKE CITY, UT 84111

EXAMINER

ZARNEKE, DAVID A

ART UNIT

PAPER NUMBER

2829

DATE MAILED: 02/01/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

## Office Action Summary

Application No.

10/618,113

Applicant(s)

JOSHI ET AL.

Examiner

David A. Zarneke

Art Unit

2829

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

### Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

### Status

- 1) ☒ Responsive to communication(s) filed on 06 December 2004.
- 2a) ☒ This action is **FINAL**. 2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

### Disposition of Claims

- 4) ☒ Claim(s) 20-47 is/are pending in the application.
- 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.
- 5) ☐ Claim(s) \_\_\_\_\_ is/are allowed.
- 6) ☒ Claim(s) 20-47 is/are rejected.
- 7) ☐ Claim(s) \_\_\_\_\_ is/are objected to.
- 8) ☐ Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

### Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on \_\_\_\_\_ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.  
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

### Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some \* c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

### Attachment(s)

- 1) ☐ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☐ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  
Paper No(s)/Mail Date \_\_\_\_\_.
- 4) ☐ Interview Summary (PTO-413)  
Paper No(s)/Mail Date. \_\_\_\_\_.
- 5) ☐ Notice of Informal Patent Application (PTO-152)
- 6) ☐ Other: \_\_\_\_\_.

## **DETAILED ACTION**

### ***Withdrawal of Claim Rejections - 35 USC § 112***

The amendment to the claim 20 overcomes the 35 USC § 112 claim rejection, which therefore is withdrawn.

### ***Response to Arguments***

Applicant's arguments filed 12/6/04 have been fully considered but they are not persuasive.

Applicant argues that Higgins doesn't teach forming the stud bump directly on the portion of the RDL pattern not covered by the insulating layer. Applicant argues that Higgins teaches forming a UBM pad [15] between the bumps and the trace [16].

In a related argument with respect to the newly submitted claims, applicant Higgins doesn't teach the use of a single layer RDL because of the teaching of a trace [16] and a pad [15].

The examiner asserts that applicant has misinterpreted the rejection. The UBM pad [15] is not relied upon in the rejection. The rejection uses the redistributed line [16] and the solder ball attached thereto through an opening in the insulating layer [18]. The UBM pad [15] was not used in the rejection of the claims.

In Figure 1, it is clear that the bump is formed directly on the portion of the RDL pattern [16] not covered by the insulating layer [18].

***Claim Rejections - 35 USC § 102***

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 20, 22 and 23 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Higgins, III, US Patent 6,294,405 (hereafter Higgins).

Higgins (Figure 1) teaches a method of making a wafer-level chip scale package, comprising:

- providing a chip pad (14) over a substrate (11);
- providing a re-distributed line (RDL) pattern (16) on the chip pad;
- providing an insulating layer (18) covering a portion of the RDL pattern, wherein the insulating layer comprises a non-polymeric dielectric material (2, 65+); and
- providing a stud bump (20) directly on the portion of the RDL pattern not covered by the insulating layer.

Regarding claim 22, Higgins teaches the insulating layer comprises SiN (2, 65+).

With respect to claim 23, Higgins does not teach using a UBM.

Claims 24, and 26-28 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Higgins, III, US Patent 6,294,405 (hereafter Higgins).

Higgins (Figure 1) teaches a method of making a wafer-level chip scale package, comprising:

- providing a substrate (11) with a passivation layer (12) on a portion thereof;

Art Unit: 2829

forming a chip pad (14) on a portion of the substrate not containing the passivation layer;

forming a metal layer (16) on the chip pad and a portion of the passivation layer;

forming an insulating layer (18) on a portion of the metal layer, wherein the insulating layer comprises a non-polymeric dielectric material (2, 65+); and

forming a stud bump (20) directly on the portion of the metal layer not covered by the insulating layer.

Regarding claim 26, Higgins teaches the insulating layer comprises SiN (2, 65+).

With respect to claims 27, while Higgins fails to expressly state that the insulating layer is formed without using a high temperature curing process, SiN inherently uses a low temperature curing process.

As to claim 28, Higgins does not teach using a UBM.

Claim 32 is rejected under 35 U.S.C. 102(b) as being clearly anticipated by Higgins, III, US Patent 6,294,405 (hereafter Higgins).

Higgins (Figure 1) teaches a method of making a package semiconductor device, comprising:

providing a chip pad (14) over a substrate (11);

providing a re-distributed line (RDL) pattern (16) on the chip pad;

providing an insulating layer (18) covering a portion of the RDL pattern, wherein the insulating layer comprises a non-polymeric dielectric material (2, 65+); and

providing a stud bump (20) directly on the portion of the RDL pattern not covered by the insulating layer.

Art Unit: 2829

Claim 33 is rejected under 35 U.S.C. 102(b) as being clearly anticipated by Higgins, III, US Patent 6,294,405 (hereafter Higgins).

Higgins (Figure 1) teaches a method of making a wafer-level chip scale package, comprising:

providing a packaged semiconductor device (10) containing a chip pad (14) over a substrate (11), a re-distributed line (RDL) pattern (16) on the chip pad, an insulating layer (18) covering a portion of the RDL pattern with the insulating layer comprising a non-polymeric dielectric material (2, 65+), and then providing a stud bump (20) directly on the portion of the RDL pattern not covered by the insulating layer; and

mounting the packaged semiconductor device on a circuit board (50).

Claims 34, 38-40 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Higgins, III, US Patent 6,294,405 (hereafter Higgins).

Higgins (figure 1) teaches a method for making wafer-level chip scale package, comprising:

providing a chip pad [12] over a substrate [11];

providing a re-distributed line (RDL) pattern [16] on the chip pad;

providing an insulating layer [18] covering a portion of the RDL pattern; and

providing a stud bump [20] on the portion of the RDL pattern not covered by the insulating layer without using an under bump metal.

Regarding claims 38-40, Higgins teaches the insulating layer [18] comprises a non- polymeric dielectric material, such as silicon nitride (2, 65+), which does not require a high temperature curing process.

Claims 41, 45-47 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Higgins, III, US Patent 6,294,405 (hereafter Higgins).

Higgins (figure 1) teaches a method for making wafer-level chip scale package, comprising:

providing a chip pad [12] over a substrate [11];  
providing a single layer re-distributed line (RDL) pattern [16] on the chip pad;  
providing an insulating layer [18] covering a portion of the RDL pattern; and  
providing a stud bump [20] on the portion of the RDL pattern not covered by the insulating layer.

Regarding claims 45-47, Higgins teaches the insulating layer [18] comprises a non- polymeric dielectric material, such as silicon nitride (2, 65+), which does not require a high temperature curing process.

### ***Claim Rejections - 35 USC § 103***

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

The factual inquiries set forth in *Graham v. John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:

1. Determining the scope and contents of the prior art.

Art Unit: 2829

2. Ascertaining the differences between the prior art and the claims at issue.
3. Resolving the level of ordinary skill in the pertinent art.
4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claim 21 is rejected under 35 U.S.C. 103(a) as being unpatentable over Higgins, III, US Patent 6,294,405, as applied to claim 20 above, and further in view of Chakravorty, US Patent 6,350,668.

Higgins fails to teach the method further comprising providing a solder ball on the stud bump.

Chakravorty (figure 8d) teaches the use of a solder ball (313) on a solder stud (311).

It would have been obvious to one of ordinary skill in the art at the time of the invention to use the ball on the stud of Chakravorty in the invention of Higgins because both methods are known equivalent techniques used to attach chips to other substrates.

The substitution of one known equivalent technique for another may be obvious even if the prior art does not expressly suggest the substitution (Ex parte Novak 16



Art Unit: 2829

USPQ 2d 2041 (BPAI 1989); In re Mostovych 144 USPQ 38 (CCPA 1964); In re Leshin 125 USPQ 416 (CCPA 1960); Graver Tank & Manufacturing Co. V. Linde Air Products Co. 85 USPQ 328 (USSC 1950).

Claims 25 and 29-31 are rejected under 35 U.S.C. 103(a) as being unpatentable over Higgins, III, US Patent 6,294,405, as applied to claim 24 above, and further in view of Chakravorty, US Patent 6,350,668.

Regarding claim 25, Higgins fails to teach the method further comprising providing a solder ball on the stud bump.

Chakravorty (figure 8d) teaches the use of a solder ball (313) on a solder stud (311).

It would have been obvious to one of ordinary skill in the art at the time of the invention to use the ball on the stud of Chakravorty in the invention of Higgins because both methods are known equivalent techniques used to attach chips to other substrates.

The substitution of one known equivalent technique for another may be obvious even if the prior art does not expressly suggest the substitution (Ex parte Novak 16 USPQ 2d 2041 (BPAI 1989); In re Mostovych 144 USPQ 38 (CCPA 1964); In re Leshin 125 USPQ 416 (CCPA 1960); Graver Tank & Manufacturing Co. V. Linde Air Products Co. 85 USPQ 328 (USSC 1950).

With respect to claims 29 and 30, Higgins fails to teach forming the stud bump by electroplating or by wire bonding (claims 29), wherein the stud bump is formed by wire bonding a Pd coated copper wire to the RDL pattern using a capillary (claim 30).

Art Unit: 2829

Chakravorty teaches the solder stud (311) can be formed using a wire bonder (9, 16+).

It would have been obvious to one of ordinary skill in the art at the time of the invention to use the wire bonder of Chakravorty in the invention of Higgins because wire bonding is a known equivalent technique used to deposit metals.

The substitution of one known equivalent technique for another may be obvious even if the prior art does not expressly suggest the substitution (Ex parte Novak 16 USPQ 2d 2041 (BPAI 1989); In re Mostovych 144 USPQ 38 (CCPA 1964); In re Leshin 125 USPQ 416 (CCPA 1960); Graver Tank & Manufacturing Co. V. Linde Air Products Co. 85 USPQ 328 (USSC 1950).

Though Chakravorty fails to teach the use of a Pd coated copper wire, it would have been obvious to use a Pd coated copper wire because it is a conventionally known in the art material used to form stud bumps.

The use of conventional materials to perform there known functions in a conventional process is obvious (MPEP 2144.07).

As to claim 31, the stud bump being coined shaped is an obvious matter of design choice. Design choices and changes of size and shape are generally recognized as being within the level of ordinary skill in the art (MPEP 2144.04(I), (IVA) & (IVB)).

Claims 35-37 are rejected under 35 U.S.C. 103(a) as being unpatentable over Higgins, III, US Patent 6,294,405, as applied to claim 34 above, and further in view of Chakravorty, US Patent 6,350,668.

Art Unit: 2829

Regarding claim 35, Higgins fails to teach the method further comprising providing a solder ball on the stud bump.

Chakravorty (figure 8d) teaches the use of a solder ball (313) on a solder stud (311).

It would have been obvious to one of ordinary skill in the art at the time of the invention to use the ball on the stud of Chakravorty in the invention of Higgins because both methods are known equivalent techniques used to attach chips to other substrates.

The substitution of one known equivalent technique for another may be obvious even if the prior art does not expressly suggest the substitution (Ex parte Novak 16 USPQ 2d 2041 (BPAI 1989); In re Mostovych 144 USPQ 38 (CCPA 1964); In re Leshin 125 USPQ 416 (CCPA 1960); Graver Tank & Manufacturing Co. V. Linde Air Products Co. 85 USPQ 328 (USSC 1950).

With respect to claims 36 and 37, Higgins fails to teach forming the stud bump by electroplating or by wire bonding (claims 29), wherein the stud bump is formed by wire bonding a Pd coated copper wire to the RDL pattern using a capillary (claim 30).

Chakravorty teaches the solder stud (311) can be formed using a wire bonder (9, 16+).

It would have been obvious to one of ordinary skill in the art at the time of the invention to use the wire bonder of Chakravorty in the invention of Higgins because wire bonding is a known equivalent technique used to deposit metals.

The substitution of one known equivalent technique for another may be obvious even if the prior art does not expressly suggest the substitution (Ex parte Novak 16

Art Unit: 2829

USPQ 2d 2041 (BPAI 1989); In re Mostovych 144 USPQ 38 (CCPA 1964); In re Leshin 125 USPQ 416 (CCPA 1960); Graver Tank & Manufacturing Co. V. Linde Air Products Co. 85 USPQ 328 (USSC 1950).

Though Chakravorty fails to teach the use of a Pd coated copper wire, it would have been obvious to use a Pd coated copper wire because it is a conventionally known in the art material used to form stud bumps.

The use of conventional materials to perform there known functions in a conventional process is obvious (MPEP 2144.07).

Claims 42-44 are rejected under 35 U.S.C. 103(a) as being unpatentable over Higgins, III, US Patent 6,294,405, as applied to claim 41 above, and further in view of Chakravorty, US Patent 6,350,668.

Regarding claim 35, Higgins fails to teach the method further comprising providing a solder ball on the stud bump.

Chakravorty (figure 8d) teaches the use of a solder ball (313) on a solder stud (311).

It would have been obvious to one of ordinary skill in the art at the time of the invention to use the ball on the stud of Chakravorty in the invention of Higgins because both methods are known equivalent techniques used to attach chips to other substrates.

The substitution of one known equivalent technique for another may be obvious even if the prior art does not expressly suggest the substitution (Ex parte Novak 16

Art Unit: 2829

USPQ 2d 2041 (BPAI 1989); In re Mostovych 144 USPQ 38 (CCPA 1964); In re Leshin 125 USPQ 416 (CCPA 1960); Graver Tank & Manufacturing Co. V. Linde Air Products Co. 85 USPQ 328 (USSC 1950).

With respect to claims 36 and 37, Higgins fails to teach forming the stud bump by electroplating or by wire bonding (claims 29), wherein the stud bump is formed by wire bonding a Pd coated copper wire to the RDL pattern using a capillary (claim 30).

Chakravorty teaches the solder stud (311) can be formed using a wire bonder (9, 16+).

It would have been obvious to one of ordinary skill in the art at the time of the invention to use the wire bonder of Chakravorty in the invention of Higgins because wire bonding is a known equivalent technique used to deposit metals.

The substitution of one known equivalent technique for another may be obvious even if the prior art does not expressly suggest the substitution (Ex parte Novak 16 USPQ 2d 2041 (BPAI 1989); In re Mostovych 144 USPQ 38 (CCPA 1964); In re Leshin 125 USPQ 416 (CCPA 1960); Graver Tank & Manufacturing Co. V. Linde Air Products Co. 85 USPQ 328 (USSC 1950).

Though Chakravorty fails to teach the use of a Pd coated copper wire, it would have been obvious to use a Pd coated copper wire because it is a conventionally known in the art material used to form stud bumps.

The use of conventional materials to perform there known functions in a conventional process is obvious (MPEP 2144.07).

***Conclusion***

**THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).


A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to David A. Zarneke whose telephone number is (571)-272-1937. The examiner can normally be reached on M-F 7:30 AM-6 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nestor Ramirez can be reached on (571)-272-2034. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Art Unit: 2829

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



David A. Zarneke  
Primary Examiner  
January 27, 2005